

ABSTRACT OF THE DISCLOSURE

A device for applying a liquid dopant solution on a wafer includes a dopant distribution device, a rotatable horizontally translatable dopant-transfer roll between a first roll position and a second roll position, and a work table for holding the wafer. The distribution device includes a dopant-transfer block and a fluid container having an open side enclosed by an edge, which open side is directed to the dopant-transfer block. The block holder is horizontally translatable between a first block position, in which the dopant-transfer block is under the open side of the fluid container, and a second block position, in which the dopant-transfer block contacts the rotatable dopant-transfer roll in a first roll position. During normal operation in a second roll position, the rotatable dopant-transfer roll contacts the wafer to provide dopant solution onto the surface of the wafer.